

Sponsor Student Grants

Increase student participation at SPIE Photomask Technology + EUV Lithography 8-11 September 2026

The Sponsored Student Grants program has been developed to encourage student participation and research contributions in the field of advanced lithography and photomask technologies. While funds last, financial support will be extended to any student wishing to attend the Photomask Technology + EUV Lithography 2026 Symposium. Priority will be given to student authors, but all students are encouraged to apply.

Sponsorship details:

- Sponsors receive logo placements in the event program, website, room slides, and onsite banners, plus access to student contact information
- Cost per sponsor: \$5,000
- Deadline: 1 July 2026

How funds will be distributed:

Funds are sent to SPIE by sponsors and held in a student grant account specifically for SPIE Photomask Technology + EUV Lithography. Registration fees will be covered for all accepted students, and each student will receive travel and lodging reimbursement until funds are depleted, with priority given first to presenting authors and last to non-authors.

Any excess funds will be transferred to future years' student grants.

Requirements for grant awardees:

- Applicants must be students.
- If the student is an author, they must submit a manuscript by the specified date.

Email Josephine Hegeberg (josephineh@spie.org) for more information or to confirm company involvement.

